

# Capacitance of Gated GaAs/Al<sub>x</sub>Ga<sub>1-x</sub>As Heterostructures Subject to In-plane Magnetic Fields

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A detailed analysis of the capacitance of gated GaAs/Al<sub>x</sub>Ga<sub>1-x</sub>As heterostructures is presented. The nonlinear dependence of the capacitance on the gate voltage and in-plane magnetic field is discussed together with the capacitance quantum steps connected with a population of higher 2D gas subbands. The results of full self-consistent numerical calculations are compared to recent experimental data.

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In modulation doped GaAs/Al<sub>x</sub>Ga<sub>1-x</sub>As heterostructures a charged channel is formed in GaAs near the interface due to the electron transfer from donors in Al<sub>x</sub>Ga<sub>1-x</sub>As. If a metal Schottky gate is evaporated on the Al<sub>x</sub>Ga<sub>1-x</sub>As surface the electron density  $N$  of the GaAs inversion layer can be controlled by the gate voltage  $V_g$ . In strong inversion and at low temperatures the impurity depletion charges are essentially fixed and the charge induced by the variation of the gate voltage goes entirely into the inversion layer. In this regime the heterostructure behaves like a capacitor with one metal electrode and the second electrode represented by the channel in GaAs.

The differential capacitance (per unit area) of a gated structure,  $C = d|e|N/dV_g$ , is traditionally [1], [4] written in the form

$$C^{-1} = C_b^{-1} + \frac{\gamma \bar{z}}{\epsilon} + \frac{1}{e^2 g}. \quad (1)$$

Here  $C_b = \epsilon/d_b$  denotes the barrier capacitance determined by the Al<sub>x</sub>Ga<sub>1-x</sub>As barrier width  $d_b$  and the dielectric constant  $\epsilon$ . The second term takes into account the distance  $\bar{z}$  of the centroid of the inversion layer charge from the interface. The numerical prefactor  $\gamma$  results from approximating (see e.g. [2] and [3]) the dependence of the subband energy  $E_0$  on  $N$  by  $dE_0/dN \propto \bar{z}$ . In GaAs/Al<sub>x</sub>Ga<sub>1-x</sub>As,  $\gamma$  lies in the interval 0.5 - 0.7. The last term of equation (1) expresses the dependence of the capacitance on the density of states  $g$  of the 2D electron gas.

Recently the capacitance of gated GaAs/Al<sub>x</sub>Ga<sub>1-x</sub>As structures has been measured with a high accuracy by Hampton et al [4], both as a function of the gate voltage and of the in-plane magnetic field. The main results of the measurements are, with a kind permission of authors, reproduced in figure 1. The aim of this paper is to present a detailed analysis of the data based on the full self-consistent numerical calculation, going beyond the validity of equation (1).

A band diagram of the charged gated structure is sketched in figure 2. Boundary conditions for the electrostatic potential  $\Phi(L_a) = 0$  and  $d\Phi/dz(L_a) = 0$  correspond to the assumption of fixed impurity depletion charges and to a charge neutrality of the whole structure. The gate voltage  $V_g$  is a difference between the chemical potential  $E_F^g/|e|$  of the gate and the chemical potential  $E_F/|e|$  of the inversion layer. At the metallic gate the chemical potential is determined essentially by the electrostatic potential  $\Phi_g$  since the difference is a constant built-in voltage of the Schottky barrier  $V_B$ . We obtain from the Poisson equation

$$\Phi_g = \frac{d_b + \bar{z}}{\epsilon} |e|N + K. \quad (2)$$

The constant  $K$  is a contribution to the potential due to frozen out impurity charges and due to the discontinuity at the GaAs/Al<sub>x</sub>Ga<sub>1-x</sub>As interface. Consequently, the gate voltage is given by

$$V_g = \frac{E_F}{|e|} + \frac{d_b + \bar{z}}{\epsilon} |e|N + K + V_B \quad (3)$$

and the reciprocal value of the capacitance reads

$$C^{-1} = C_b^{-1} + C_c^{-1} \quad (4)$$

where

$$C_c^{-1} = \frac{d}{dN} \left( \frac{\bar{z}}{\epsilon} N + \frac{E_F}{|e|^2} \right). \quad (5)$$

Thus, the gated structure capacitance can be again considered as a barrier capacitance  $C_b$  and a channel capacitance  $C_c$  in series. The reciprocal value of the channel capacitance is a sum of two terms: the electrostatic one, related to the concentration dependent position of the channel centroid in GaAs and the thermodynamical one originating from the concentration dependent chemical potential in the semiconductor. Both these quantities can also depend on the applied magnetic field.

Up to now a very general analysis of the gated structure capacitance has been carried out regardless the detail properties of the inversion layer. In the next step we summarize basic formulae describing the layer electron structure.

In a zero magnetic field the standard envelope function approximation yields the Schrödinger equation for a conduction electron

$$\left( \frac{\mathbf{p}^2}{2m} - |e|V_{conf}(z) - E \right) \psi(\mathbf{r}) = 0 \quad (6)$$

where the confining potential  $V_{conf}$  is a sum of the electrostatic potential  $\Phi$ , obtained within the Hartree approximation, and the exchange-correlation term  $V_{xc}$ , describing the effects of electron-electron interaction beyond the Hartree approximation. We use the simple analytic parametrization of  $V_{xc}$  within the local-density-functional formalism, suggested by Ruden and Döhler [5]. Thus, the self-consistent solution to coupled Schrödinger equation (6) and Poisson equation for the electrostatic potential  $\Phi$  gives the electron structure of the conduction channel, including the many-body corrections to  $E_0$  and  $\bar{z}$  [6].

Looking for the eigenfunction of the equation (6) in the form

$$\psi(\mathbf{r}) = \frac{1}{\sqrt{S}} \exp(ik_x x + ik_y y) \phi_n(z) \quad (7)$$

we obtain 2D subbands of allowed energies

$$E(k_x, k_y, n) = \frac{\hbar^2}{2m} (k_x^2 + k_y^2) + E_n. \quad (8)$$

Equations (7) and (8) are the mathematical expression for the separability of the free in-plane ( $x, y$ -direction) and bound out-of-plane ( $z$ -direction) components of the electron motion.

Firstly, let us assume only the lowest subband to be occupied. Then, due to the parabolic dispersion of the in-plane energy, the 2D density of states per unit area  $g$  is a universal constant  $m/\pi\hbar^2$  and the 2D concentration of the electron layer reads

$$N = g(E_F - E_0) \quad (9)$$

where  $E_0$  is the lowest energy of the bound out-of-plane motion.

The average position  $\bar{z}_0$  of the electron layer is determined by the  $z$ -dependent part of the wavefunction as

$$\bar{z}_0 = \int z |\phi_0(z)|^2 dz. \quad (10)$$

Now, the attention can be turned back to the heterostructure capacitance. Due to (9) and (10) quasi-analytical relations for both the thermodynamical and electrostatic parts of the reciprocal channel capacitance are available. The electrostatic term is related exclusively to the out-of-plane component of the electron motion. In the thermodynamical term both components of the motion play a role. However, according to (9) their influence is independent and we obtain the channel capacitance in the form

$$C_c^{-1} = \frac{\bar{z}_0}{\epsilon} + \frac{N}{\epsilon} \frac{d\bar{z}_0}{dN} + \frac{\pi\hbar^2}{m|e|^2} + \frac{1}{|e|^2} \frac{dE_0}{dN}. \quad (11)$$

Different 2D gas concentrations (or gate voltages) directly yield different shapes of the confining potential  $V_{conf}$  and thus the bound state eigenenergy  $E_0$  is modified. For confining potentials which do not depart substantially from an exactly triangular well one obtains the scaling laws  $\bar{z}_0 \propto N^{-1/3}$  and  $E_0 \propto N^{2/3}$  [3], from them the relation  $dE_0/dN \propto \bar{z}_0$  and the equation (1) is regained. The quantitative deviations can be expected for more realistic shape of the confining potential of standard gated structures and, in the case of gated symmetric wells or inverted structures, the above mentioned scaling law is not valid at all. Therefore both  $dE_0/dN$  and  $\bar{z}_0$  have to be determined independently in the course of the self-consistency procedure.

In magnetic fields parallel to the heterostructure interface the separability between the in-plane and out-of-plane components of the channel electron motion is lost. Assuming the magnetic field  $\mathbf{B} \parallel y$  the wavefunction  $\phi(z)$  becomes  $k_x$  dependent. As discussed in more details in [7–9], this results in a charge redistribution of the 2D gas and in a modification of 2D subbands. The centroid  $\bar{z}_0$  of the channel first shifts to the bulk GaAs and then, after the magnetic field reaches a critical value, it returns back to the heterostructure interface. The deviation of the energy dispersion  $E(k_x)$  from the parabolic shape yields a density of states which form depends both on the magnetic field and the electron concentration [10]. Finally, the subband edge is shifted to higher energies by the in-plane field. It follows from the above mentioned effects on the electron structure that the electrostatic term and both contributions to the thermodynamical term are modified by the in-plane magnetic field in a rather complicated way.

A sufficient amount of information about the heterostructure capacitance has been given to open the last problem we want to deal with. Except the very general formula (5) previous conclusions are restricted to 2D electron systems with one occupied subband. Now we extend the discussion to multi-subband systems since the filling or depleting of the higher subband is reflected in the observed capacitance quantum steps. A heterostructure where the number of occupied subbands is changed by the gate voltage in the absence of the magnetic field will be considered. A discussion concerning the in-plane magnetic field induced depopulation of higher subbands would be analogous.

In the case of two occupied subbands we obtain the channel capacitance

$$C_{2c}^{-1} = \frac{\bar{z}}{\epsilon} + \frac{N}{\epsilon} \frac{d\bar{z}}{dN} + \frac{\pi\hbar^2}{2m|e|^2} + \frac{1}{|e|^2} \frac{d\bar{E}}{dN} \quad (12)$$

in the form similar to (11) but with  $\bar{z}_0$  and  $E_0$  replaced by

$$\bar{z} = \frac{\bar{z}_0 N_0 + \bar{z}_1 N_1}{N}, \quad (13)$$

$$\bar{E} = \frac{E_0 + E_1}{2}. \quad (14)$$

The quantities  $N_0 = (E_F - E_0) m/\pi\hbar^2$  and  $N_1 = (E_F - E_1) m/\pi\hbar^2$  are the concentrations of electrons in the first and second subband,  $N_0 + N_1 = N$ .

Two terms in equations (11), (12) do not contain the derivatives with respect to  $N$ . The first one, proportional to the centroid coordinate, does not cause any step when (11) is replaced by (12) after reaching the critical concentration  $N_c$  since  $\bar{z}(N_c + 0) = \bar{z}_0(N_c - 0)$ . The step in the second term is a universal constant and reflect the fact that the density of states is doubled above  $N = N_c$ . The additional steps come from the terms with derivatives which can be expressed for  $N > N_c$  similarly as for the case of single subband occupancy with a help of  $d\bar{z}_i/dN$ ,  $d\bar{E}_i/dN$ ,  $i = 0, 1$ .

The previous analysis shows the principal reasons for the gate voltage or in-plane magnetic field dependency of the one-subband channel capacitance as well as for steps in capacitance when a higher subband is populated. To obtain results comparable to experimental data full self-consistent numerical calculations, treating the electron-electron interaction beyond the Hartree approximation both in zero and non-zero magnetic fields, are unavoidable since the simple scaling rule leading to (1) is quite unrealistic in the presence of the magnetic field and for the double subband occupancy.

Figure 1 presents data of low temperature capacitance measurements on an  $\text{Al}_x\text{Ga}_{1-x}\text{As}/\text{GaAs}$  sample with  $x = 0.3$  and channel concentrations from about  $1 \times 10^{11}$  to  $4 \times 10^{11} \text{ cm}^{-2}$ . Since the shape of the confining potential depends also on depletion charges parameters which are not exactly known we performed numerical calculations for  $N_a = 4 \times 10^{14} \text{ cm}^{-3}$  and several frozen-in depletions lengths  $L_a$ . Due to an unambiguous relation between the gate voltage dependency of the capacitance, including the position of the quantum step, and the shape of the quantum well it is possible to use the experimental curve measured at  $B_y = 0$  for determining  $L_a$ . This way we obtained  $L_a = 550 \text{ nm}$ . (We do not discuss the height of the quantum step since a current leakage occurred at the gate voltage  $V_g = +150 \text{ mV}$ , which might quantitatively modify the measured voltage dependency of the capacitance.) As shown in figure 3, if the theoretical and experimental gate voltage dependencies at the zero magnetic field are in a good agreement, the theory predicts, with a very reasonable accuracy, the behaviour of the capacitance for non zero in-plane magnetic fields. The impurity scattering of electrons together with the roughness of the interface are responsible for smearing of the quantum step, we simulate their influence by introducing the Dingle temperature  $T_D \approx 1 \text{ K}$ . The effect of the magnetic field on both the electrostatic and thermodynamical terms in the reciprocal channel capacitance is shown in figure 4 to illustrate the violation of the formula (1). Note that the term  $1/e^2 dE_F/dN$  cannot be simplified due to the field and concentration dependence of the density of states.

In conclusion, we want to point out that the capacitance measurements provide a lot of information about 2D electron gas properties but the data have to be interpreted very carefully. It is well known that in structures shown

in figure 3 the 2D channel with higher concentration is confined closer to the GaAs/ $\text{Al}_x\text{Ga}_{1-x}\text{As}$  interface resulting in a smaller distance between electrodes. However, this effect is not reflected directly in the capacitance due to simultaneous shift of bound states energies. Similarly, the charge redistribution by the in-plane magnetic field is accompanied with the shift of subband edges. Moreover, the modification in the density of states contributes to the magnetic field induced changes in the capacitance. Finally, the discontinuities in the 2D density of states are responsible only partially for the capacitance quantum steps. We have seen that also the ratio between the filling of subbands and the relative positions of electron layers in each subband play an important role.

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FIG. 1. Experimental curves of the capacitance as a function of the gate voltage and of the in-plane magnetic field determined by Hampton et al [4].

FIG. 2. Schematic band diagram for a gated GaAs/ $\text{Al}_x\text{Ga}_{1-x}\text{As}$  heterostructure.

FIG. 3. Self-consistently calculated gate voltage and in-plane magnetic field dependencies of the relative capacitance. For  $B = 0$  the results for three depletion lengths of acceptors are presented,  $N_a = 4 \times 10^{14} \text{ cm}^{-3}$ . Magnetic field dependencies are plotted only for selected gate voltages and  $L_a = 550 \text{ nm}$  to make comparison of experimental and theoretical curves easier.

FIG. 4. An increment of the reciprocal channel capacitance  $\delta C_c^{-1} = C_c^{-1}(B) - C_c^{-1}(0)$  (dotted line) in the magnetic field, decomposed in a thermodynamical term  $1/e^2 d\delta E_F/dN$  and two contributions  $N/\epsilon d\delta \bar{z}/dN$ ,  $\delta \bar{z}/\epsilon$  to the electrostatic term.